

JC-060 U.S. PRO
 09/051601
 10/60/150

ISSUE CLASSIFICATION	
Class	Subclass

PATENT NUMBER

U.S. **UTILITY** Patent Application

O.I.P.E. FA SCANNED 882 Q.A. CS-2	PATENT DATE
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APPLICATION NO. 09/851601	CONT/PRIOR D	CLASS 427	SUBCLASS	ART UNIT 1762	EXAMINER
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APPLICANTS

Timothy Skene
Matthew Lowrey
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TITLE

Fabrication of silicon nanowire structures by electron beam evaporation

PTO-2040
12/99[illegible]

<input type="checkbox"/> TERMINAL DISCLAIMER	DRAWINGS			CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.
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	_____ (Primary Examiner) _____ (Date)	Amount Due	Date Paid		
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